In The Matter Of:

Taiwan Semiconductor Manufacturing Co., Ltd. v. Godo Kaisha IP Bridge 1

Stanley R. Shanfield, Ph.D. July 25, 2018

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IP Bridge Exhibit 2232 TSMC v. Godo Kaisha IP Bridge 1



God	o Kaisha IP Bridge 1		Jul	y 25, 201
	Page 1			Page 3
1	UNITED STATES PATENT AND TRADEMARK OFFICE	1	APPEARANCES: (continued)	
2	BEFORE THE PATENT TRIAL AND APPEAL BOARD	2		
3	Case Nos. IPR2017-01841, IPR2017-01843	3	Wolf, Greenfield & Sacks, P.C.	
4	Patent 7,893,501	4	By: Gerald B. Hrycyszyn, Esq.	
5	x	5	and Joshua J. Miller, Esq.	
6	TAIWAN SEMICONDUCTOR MANUFACTURING	6	600 Atlantic Avenue	
7	CO., LTD.,	7	Boston, MA 02210-2206	
8	Petitioner,	8	(617) 646-8000	
9	v.	9	gerald.hrycyszyn@wolfgreenfield.com	
10	GODO KAISHA IP BRIDGE 1,	10	jmiller@wolfgreenfield.com	
11	Patent Owner.	11	for the Patent Owner.	
12	x	12		
13	VOLUME I Pages 1-181	13		
14		14		
15	DEPOSITION OF STANLEY R. SHANFIELD, Ph.D.	15		
16	Wednesday, July 25, 2018, 9:03 a.m.	16		
17	Wilmer Cutler Pickering Hale and Dorr LLP	17		
18	60 State Street	18		
19	Boston, Massachusetts 02109	19		
20		20		
21		21		
22	Reporter: Kimberly A. Smith, CRR, CRC, RDR	22		
23	Realtime Systems Administrator	23		
24	O'Brien & Levine Court Reporting Solutions	24		
	Page 2			Page 4
1	APPEARANCES:	1	INDEX	
2		2		
3	Wilmer Cutler Pickering Hale and Dorr LLP	3	WITNESS: Stanley R. Shanfield, Ph.D.	
4	By: Michael H. Smith, Esq.	4		
5	1875 Pennsylvania Avenue, N.W.	5	EXAMINATION	Page
6	Washington, D.C. 20006	6	Cross-Examination by Mr. Hrycyszyn	6
7	(202) 663-6000	7	AFTERNOON SESSION	
8	michaelh.smith@wilmerhale.com	8	Cross-Examination by Mr. Hrycyszyn	59
9	and	9	Redirect Examination by Mr. Smith	143
10	Wilmer Cutler Pickering Hale and Dorr LLP	10	Recross-Examination by Mr. Hrycyszyn	157
11	By: Scott Bertulli, Esq.	11	Redirect Examination by Mr. Smith	167
12	60 State Street	12	Recross-Examination by Mr. Hrycyszyn	173
13	Boston, MA 02109	13		
14	(617) 526-6000	14	EXHIBITS FOR IDENTIFICATION:	
		15	Exhibit Description	Page
To	SCOTT.Dertulll@wllmernale.com			5
15 16	scott.bertulli@wilmerhale.com and		Exhibit 1002 Previously marked	91
16	and	16	Exhibit 1002 Previously marked Exhibit 1025 Previously marked	91 136
16 17	and Taiwan Semiconductor Manufacturing Co., Ltd.	16 17	Exhibit 1025 Previously marked	136
16 17 18	and Taiwan Semiconductor Manufacturing Co., Ltd. By: Willy Chang, Esq.*	16 17 18	Exhibit 1025 Previously marked Exhibit 1026 Previously marked	136 139
16 17 18 19	and Taiwan Semiconductor Manufacturing Co., Ltd. By: Willy Chang, Esq.* 8, Li Hsin Road	16 17 18 19	Exhibit 1025 Previously marked Exhibit 1026 Previously marked Exhibit 1027 Previously marked	136 139 82
16 17 18 19 20	and Taiwan Semiconductor Manufacturing Co., Ltd. By: Willy Chang, Esq.* 8, Li Hsin Road 6 Hsinchu Science Park	16 17 18 19 20	Exhibit 1025 Previously marked Exhibit 1026 Previously marked Exhibit 1027 Previously marked Exhibit 1201 Previously marked	136 139 82 9
16 17 18 19 20 21	and Taiwan Semiconductor Manufacturing Co., Ltd. By: Willy Chang, Esq.* 8, Li Hsin Road 6 Hsinchu Science Park Hsinchu 30078, Taiwan	16 17 18 19 20 21	Exhibit 1025 Previously marked Exhibit 1026 Previously marked Exhibit 1027 Previously marked Exhibit 1201 Previously marked Exhibit 1202 Previously marked	136 139 82 9 35
16 17 18 19 20	and Taiwan Semiconductor Manufacturing Co., Ltd. By: Willy Chang, Esq.* 8, Li Hsin Road 6 Hsinchu Science Park	16 17 18 19 20	Exhibit 1025 Previously marked Exhibit 1026 Previously marked Exhibit 1027 Previously marked Exhibit 1201 Previously marked	136 139 82 9



God	lo Kaisha IP Bridge 1		July 25, 2018
	Page 5		Page 7
1	EXHIBITS FOR IDENTIFICATION: (continued)	1	BY MR. HRYCYSZYN:
2	Exhibit Description Page	2	Q. Do you recall providing declarations in
3	Exhibit 2005 Previously marked 127	3	this IPR?
4	Exhibit 2009 Previously marked 112	4	A. Sure.
5	Exhibit 2010 Previously marked 120	5	Q. Do you remember opining on "film" in this
6	Exhibit 2023 Annotated Figure 12 of 126	6	IPR?
7	Igarashi (same as Ex. 2231)	7	A. Yes.
8	Exhibit 2202 Previously marked 68	8	Q. So I'm asking you, what was your
9	Exhibit 2231 Annotated Figure 12 of 126	9	understanding of that word "film" that you used in
10	Igarashi (same as Ex. 2023)	10	your declarations?
11		11	A. Well, let me take a look. Maybe the best
12		12	place to look is in the reply.
13		13	So, for example, in paragraph 18 on
14		14	page 11 of my reply declaration this is the
15		15	1843 give you a chance to find it Figure 5
16		16	shows a silicon nitride film 20 and that layer 20
17		17	is in this Misra reference, is one example of
18		18	"film." It's silicon nitride Si 3 and 4, some
19		19	hydrogen in there. And it's amorphous layer
20		20	material. It's been deposited in one manufacturing
21		21	step.
22		22	MR. HRYCYSZYN: Object as nonresponsive.
23	Original exhibit retained by reporter to be returned	23	BY MR. HRYCYSZYN:
24	to Wolf, Greenfield & Sacks	24	Q. So my question is, what was your working
	Page 6		Page 8
1	STANLEY R. SHANFIELD, Ph.D.,	1	understanding of the term "film" that you applied in
2	having been satisfactorily identified by the	2	opining on the claims in this case?
3	production of his driver's license, and	3	A. The answer I gave you is an example of that
4	duly sworn by the court reporter, was deposed	4	and I defined or I understood layer 20 as shown
5	and testified as follows:	5	here is an example of a silicon nitride film. It's
6	CROSS-EXAMINATION	6	a layer or layers of material, in this case, that
7	BY MR. HRYCYSZYN:	7	are silicon nitride or you know, that are on top
8	Q. Good morning, Dr. Shanfield.	8	of each other or a single layer, silicon nitride
9	A. Good morning.	9	being silicon and nitrogen and some hydrogen.
10	Q. What is a film in the context of the	10	And it's been deposited in one
11	'501 patent?	11	deposition step. And generally film is a reference
12	A. So maybe in the '501 patent, you could show	12	to something or a layer that's fairly thin.
13	me where that word is used and I could give you a	13	Q. So your working understanding of a film is
14	better answer.	14	it's a layer that is relatively thin, or fairly
15	Q. So you don't recall in the context of the	15	thin; is that accurate?
16	'501 patent where "film" is used or where your	16	MR. SMITH: Objection.
17	declarations in this IPR have been submitted and	17	THE WITNESS: No.
18	focus on?	18	BY MR. HRYCYSZYN:
19	MR. SMITH: Objection.	19	Q. Then what is your working understanding of
20	THE WITNESS: So I think I can give you	20	the term "film" as it is used in the claims of the
21	a more accurate and more complete answer if I have	21	'501 patent?
22	the specific, at least the paragraph or sentence	22	A. Well, if you give me the '501 patent, I can
23	that refers to "film."	23	refer to a specific instance of that in the patent
24		24	itself. I'd appreciate that. I can't do it by

Godo Kaisha IP Bridge 1 July 25, 2018 Page 9 Page 11 memory. the working definition of "film" that you used in 1 Q. So you have --2 this IPR? 2 A. I picked out something in my declaration 3 MR. SMITH: Objection. 3 that is a film to give you a sense of my THE WITNESS: No. 4 understanding of that film. BY MR. HRYCYSZYN: 5 Q. So you can't provide me a definition of Q. So then what is the extent of the working 6 6 "film" as you understand it and applied in your 7 definition you used of "film" in this case? 7 opinions related to the '501 patent? A. So like I explained, in order to give you a 8 MR. SMITH: Objection. good answer, I want to talk about specific context. 9 **THE WITNESS:** No, that's not true. I --In this case, I talked about the gate insulating 10 10 **BY MR. HRYCYSZYN:** film. I can answer any question about, you know, 11 11 Q. Well, that's what I'm asking you to other film that is mentioned in the '501, explain my 12 12 provide. But so far -working understanding of it. 13 13 A. I'm asking you for the patents so I can Q. So let me draw your attention to 14 14 show you clearly what I mean. paragraph 19 in your reply brief. 15 15 Q. I'm introducing what has been previously A. Paragraph 19 in which? 16 16 marked as Exhibit 1201. It is titled U.S. Patent Q. I'm introducing what has been previously 17 17 marked as Exhibit 1232, "Reply declaration of No. 7,893,501. 18 18 19 Do you recognize that document? Stanley R. Shanfield, Ph.D.," in Case 19 20 A. Yes. No. IPR2017-1843. 20 Q. What is it? 21 A. I have a copy. 21 A. This is the '501 patent. Q. Do you recognize that document? 22 22 Q. Do you remember opining on that patent in A. Yes. 23 23 24 this IPR? Q. What is it? 24 Page 10 Page 12 A. Yes, of course. A. This is my reply declaration for Case 1 1 2 Q. Do you remember providing opinions related 2 No. IPR2017-01843. to films in your opinion in this IPR? Q. Let me draw your attention to paragraph 19. 3 3 A. I think I answered that. Yes. Are you there? 4 4 Q. What was your working understanding of the A. Um-hum, yes. 5 5 term "film" in providing those opinions? Q. Have you had a chance to read that 6 6 A. If you go to Claim 1 that's in the 7 7 paragraph? '501 patent. And I'll start with "a gate electrode 8 A. One moment. Yes. 8 formed on a [sic] gate insulating film." So in this 9 Q. So here you refer to two layers of a single 9 case -- and this is the reason I need a specific 10 film, right? 10 reference -- a gate insulating film here is silicon A. What I said was, "no person of ordinary 11 11 skill . . . would have considered silicon nitride dioxide grown or some insulating film grown on 12 12 silicon, but it's typically silicon dioxide, and the film 20 and spacers 23 to be two layers of a single 13 13 gate sits on top of that thin layer. film." 14 14

In this case, it's quite thin. It's a nanometer scale. And it separates the gate because it's insulating from the active region. So a gate insulating film formed on the active region, and the gate electrode formed on the gate insulating film.

In that context, the film is a siliconoxygen compound that's a few nanometers thick deposited or grown in a single deposition step. And that's my understanding in this case.

Q. So that's the extent of the -- let's say,

it's internal stress film -- can include multiple 18 layers, as long as they apply stress to the 19 substrate as a whole. So there can be layers as 20 long as they apply stress to the whole. 21

Q. So I'm asking about the definition of 22

23 "film" more generally. So can two layers make up a film generally?

Q. Do you agree that two layers can form a

A. The '501 says that a film -- in that case

single film?

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Page 15 Page 13 MR. SMITH: Objection. criteria -- what appear to be three criteria: 1 **THE WITNESS:** Well, in the sense that I process steps, functions, and structures. 2 just described it, yes. The multiple -- they can 3 Do you see that? 3 have multiple layers as long as each of the layers A. Those were -- that's a summary of some of applies a stress to the substrate. the reasons why, in my opinion, no one of ordinary 5 BY MR. HRYCYSZYN: skill in the art would have thought of these films. 6 6 Q. So are you indicating that films, as the 7 The film 20, the silicon nitride film and spacer, is 7 term "films" is used in the claims of the two layers of the same film. '501 patent, is limited to stress films? 9 Q. So for two adjacent layers to be considered 9 MR. SMITH: Objection. the same film, is it your opinion that they must be 10 10 THE WITNESS: No. the same structure formed through the same process 11 11 BY MR. HRYCYSZYN: and perform the same function? 12 12 Q. So the films that are used in the context MR. SMITH: Objection. 13 13 of the '501 patent claims are broader than just **THE WITNESS:** That's some of the reasons 14 14 films that apply stress, correct? why I think someone of ordinary skill would not view 15 15 A. As I described earlier, the gate insulating two adjacent films to be two layers of a single 16 16 film is not a film intended to apply stress. It's 17 film. 17 BY MR. HRYCYSZYN: intended to put an insulator between the gate and 18 18 19 the substrate and reduce -- and keep the density of 19 Q. So in addition to those three criteria --20 charge states low in that interface between the film same process, same structure, same function -- are 20 and the active region. So clearly, no, that's not 21 there other criteria that you believe are required 21 the only function of a film. for two adjacent layers to be considered the same 22 22 There are many functions in general. 23 film? 23 24 But for the specifics of the '501, that's an example 24 MR. SMITH: Objection. Page 14 Page 16 **THE WITNESS:** I can think of other ones. of something that's not a stress film. 1 Q. So then in the context of the '501 patent 2 2 yes. claims, can films include more than one layer? BY MR. HRYCYSZYN: 3 3 A. I think I answered that. I said that the 4 Q. What other ones would those be? internal stress films in the '501 don't have to be a A. For example, the film could be different 5 single layer. They can be multiple layers, but as material. 6 6 Q. Any other criteria that you think applies 7 long as each of them applies stress to the substrate 7 as a whole. in determining whether adjacent layers are the same 8 Q. So you answered the question specific to 9 film? 9 stress films. But the claims aren't limited to MR. SMITH: Objection. 10 10 stress films. My question is, in general, do films THE WITNESS: I -- at the moment --11 11 require -- or let me rephrase that. I mean, I can talk about chemical composition. 12 12 So in the context of the '501 patent So they may have the same description, but the 13 13 claims, can films include more than one layer? deposition method being different ends up producing 14 A. As I mentioned, in the two places where a film that is going to be different in the detailed 15 15 films are mentioned in the '501, in one case, chemistry. 16 16 internal stress films, the '501 patent explicitly As an example, a film deposited with a 17 17 says that a single -- that the films do not have to plasma-enhanced CVD system always has hydrogen as 18 18 be a single layer. They can be multiple layers. one of the constituents in the amorphous structure. 19 19

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Q. So let me draw your attention back to

paragraph 19 in your 1843 reply declaration.

Q. So in that paragraph, you talk about three

Do you see that paragraph?

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consider.

And a high temperature CVD that's not using plasma

tends to have a much lower level of hydrogen. So I

Once again, I think these are reasons,

think that would be yet another aspect that I'd

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